

# IC & Board Assembly and Reliability

## Industry Co-Development Center (ICC) with Industry Consortium for Next Gen Research and Workforce

Nilesh Badwe, IIT Kanpur (Lead)

Shiv Govind Singh, IIT Hyderabad (Co-Lead)



&

Pradeep Vempaty, Micron (Industry Lead)

Ravi Bhatkal, MacDermid Alpha (Industry Co-Lead)



&

Vanessa Smet, Georgia Tech University

Shubhra Bansal, Purdue University



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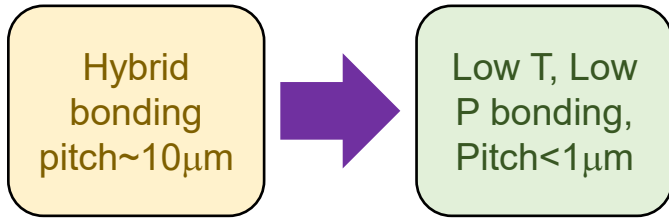
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# Next Gen Industry Need and R&D Areas

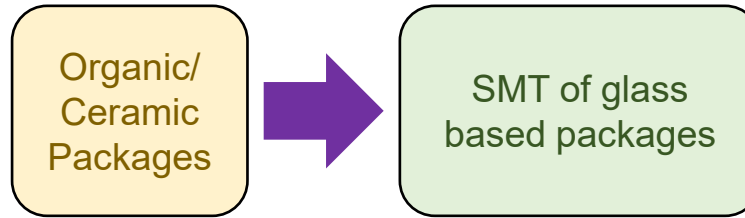
## IC Assembly

## Board Assembly

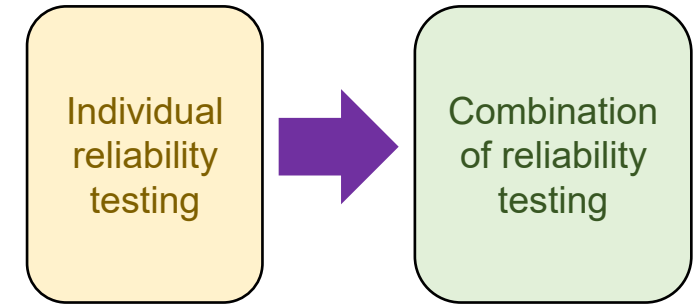
## Reliability



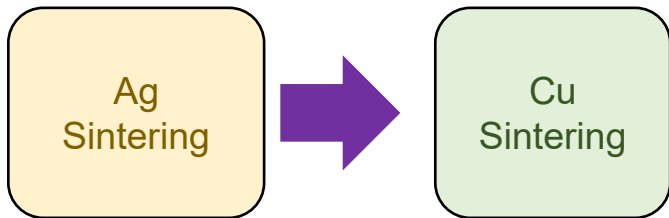
Computing



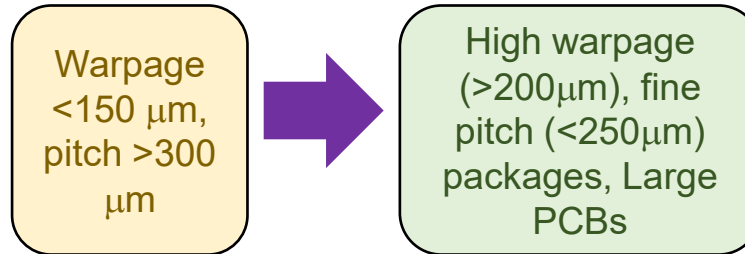
Computing and 6G



Computing and Power Electronics



Power Electronics

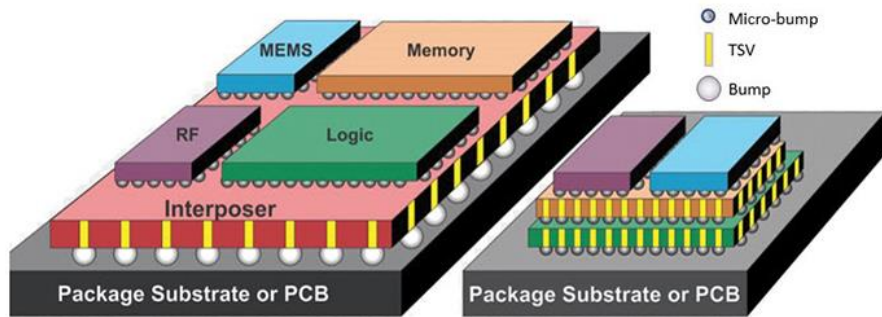


Computing

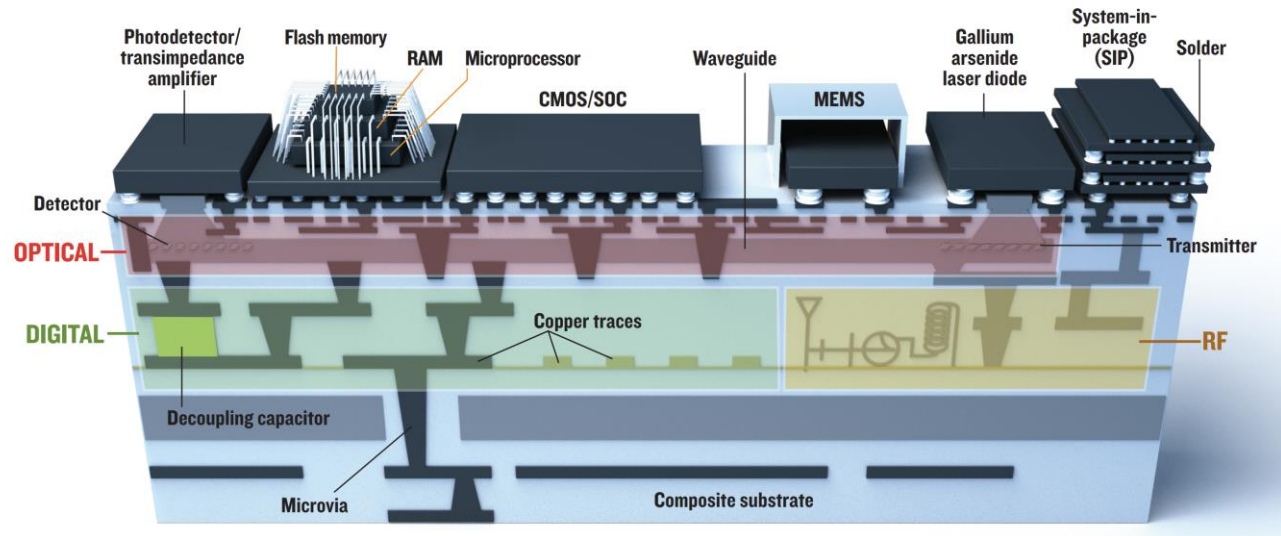
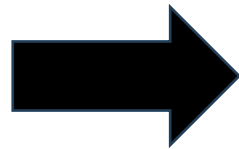
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# Current State of the Art vs Proposed Futuristic Solution



2.5D and 3D Packaging



Multiple different types of modules on a single substrate within acceptable warpage limits meeting reliability requirements

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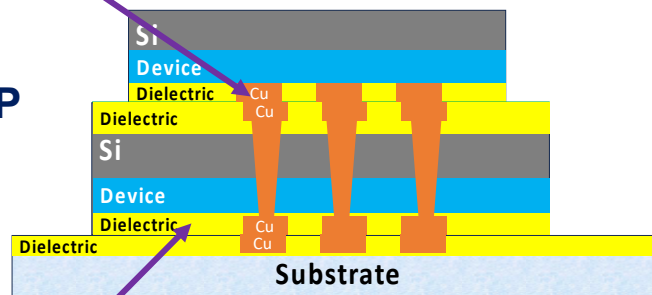


# Research Vision: Strategic Research Focus Areas

**Cu-Cu (Hybrid) bonding for IC Assembly**

Nilesh Badwe, IITK  
Shiv Govind Singh, IITH  
Poonam Sundriyal, IITKGP

**Computing and AI**



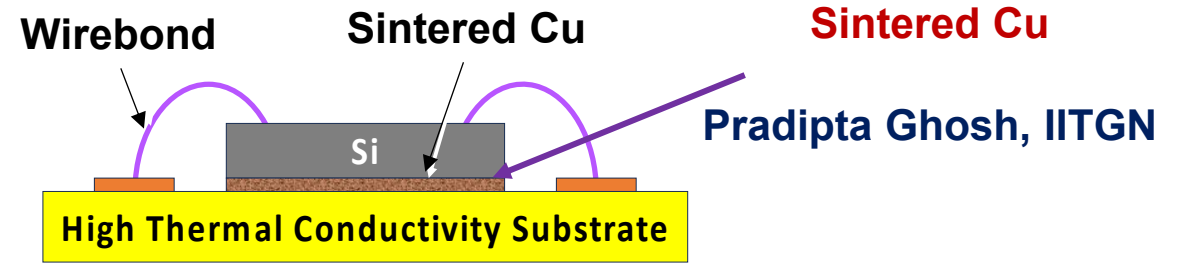
**Dielectric materials (Underfills, Mold)**

Deepak Arora, IITJ

**Board Assembly**

Nilesh Badwe, IITK

**Power Electronics**



**Sintered Cu**

Pradipta Ghosh, IITGN

**Die Attach**

**Electrical Reliability**

Shiv Govind Singh, IITH  
Shanthi Prince, SRM

**Thermomechanical Reliability**

Nilesh Badwe, IITK  
Ajay Kumar, IIT  
Pradipta Ghosh, IITGN

# ICC Team: India-wide, multidisciplinary Faculty, Global Collaborators and Industry Partners

## Core Faculty Team

(Lead)



**Nilesch Badwe**  
(MSE, IITK)

IC Assembly, Board Assembly, Thermo-mechanical reliability

(Co-lead)



**Shiv Govind Singh**  
(EE, IITH)

IC Assembly, Electrical reliability



**Pradipta Ghosh**  
(MSE, IITGN)

Sintered Cu



**Poonam Sundriyal**  
(ME, IITKGP)

Surface modification for IC Assembly



**Pradeep Dixit**  
(ME, IITB)

Low temp and TLP bonding



**Deepak Arora**  
(CHE, IITJ)

Polymeric materials inc. underfill, molds



**Shanthi Prince**  
(EE, SRM)

PCB design and reliability



**Ajay Kumar**  
(ME, IITT)

Reliability of solders

## Cross-SRA Faculty with relevant expertise

**Pradeep Dixit**  
(ME, IITB)  
Substrates

**Bhagwati Prasad**  
(MSE, IISc)  
Materials

**Tarun Agarwal**  
(EE, IITGN)  
Predictive modeling and design



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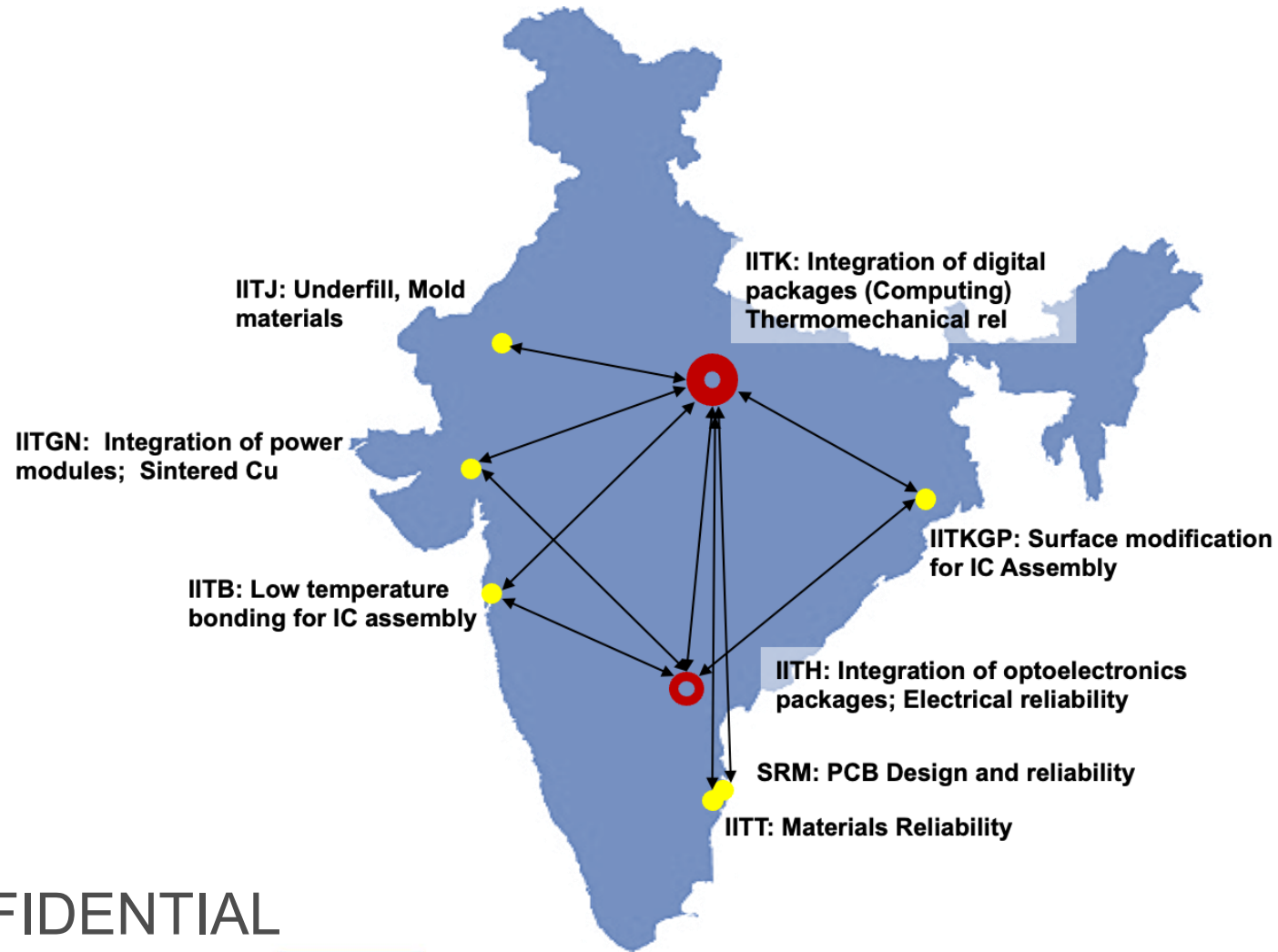


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# Hub and Spoke Model



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# Global Academic Collaborators



**Prof. Vanessa Smet**  
Georgia Tech

- 3-D integration
- Interconnection and assembly processes
- SLID / TLP bonding
- All-Cu interconnections
- Low-temperature bonding
- Reliability



**Prof. Shubhra Bansal**  
Purdue University

- Heterogeneous Integration & Advanced Packaging (sub-10  $\mu\text{m}$  pitch interconnects, low-loss interposers)
- Harsh Environment Electronics Integration (high temperature Pb-free solders and nano-thermal interfaces)



## COMPANY'S INTEREST IN RESEARCH & WORKFORCE IN THE ICBAR ICC

	Company	Research Interest	Company Lead
IDMs and OEMs	Micron	Interconnects for FLI and SLI applications, reliability assessment	Pradeep V
	Intel	Cu-Cu bonding and board assembly for glass-based packages, low conductivity interconnects, low temp assembly, board assembly for complex shape packages and large PCBs, reliability	Arun C
	AMD	Cu-Cu bonding on glass substrates	Raja S
	Western Digital	Interconnects for FLI and SLI applications	Vinoth C
	Tata	Sintered Cu, Interconnect reliability	Kirubalan N
	Toyota	Sintered Cu, Combination of reliability testing	Shailesh J
	Infineon	Interconnects and reliability for power electronics	Vinay S
Material Suppliers	MacDermid Alpha	High reliability interconnects for low temperature applications, Sintered Cu, Board assembly and reliability	Ravi B
	Indium		Andy M
	Baba Fine Chem		Rakesh G
Equipment Suppliers	BESI	Cu-Cu bonding, Metrologies for improved processes and equipment accuracy	Jonathan A
	Lam Research		Chee-Ping L
Design	Ansys	Material properties characterization for reliability modelling	Kajal K

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# Educational Programs

## Current courses:

- Packaging courses @ IITK, IITB, IITKGP, IISc
- MTech Degree “Integrated Circuits and Microsystems Packaging” @ IITH
  - Introduction to IC Packaging
  - Fundamentals of IC Packaging Assembly and Manufacturing
  - IC Package Design for Manufacturing
  - Fracture and fatigue in electronic packaging
  - IC Fabrication Technology
  - Materials for Packaging
  - Electronic Package Design
  - Heat transfer in electronic packaging
  - IC Assembly and Characterization Lab
  - Experimental stress analysis Lab

## Expected Workforce Development

Year	5 Years	10 Years
B Techs	30	60-75
M Techs	30	60-75
PhDs	20	40-50

1 B.Tech., 1 M.Tech. and 1 Ph.D. student per project

### Duration:

B.Tech. student: 1 Year  
M.Tech. student: 2 Years  
Ph.D. student: 5 Years

## Future Plan:

- Online MTech
- Post-Graduate level:
  - Masters and PhD students working on industry relevant challenges
  - A dedicated course focusing on the IC & Board Assembly and Reliability
  - New courses on Statistical Process control
  - Online courses/workshops
- Undergraduate level:
  - Elective courses
  - Hands-on training on IC assembly, Board Assembly and different reliability techniques through lab courses



# IIT Kanpur Packaging Course

No.	Topics	Hours
1	Overview of IC Fabrication, Moore's law, Introduction to Semiconductor Packaging, Packaging eras, Moore's law for packaging, 2.5D and 3D packaging technologies, Types of packages (DIP, QFN, QFP, LCC, LGA, PGA, BGA)	5
2	Design aspects of packaging: Electrical design for signal and power integrity, Materials and manufacturing of passive components, Heat transfer in packaging/Thermal design, Fundamentals of test	6
3	Substrate architecture, Basics of ceramics, organic, glass, and silicon-based package substrates	4
4	Die-prep processing: backgrinding and dicing, Chip-to-package interconnections and assembly, Encapsulation: Underfill and mold materials	6
5	Fundamentals of board assembly: Types of PCBs, PCB design, Materials and processes in board assembly, SMT defects and mitigation paths, Fluxes, Solder alloys (Sn-Pb, SAC, SnBi, high reliability), Solder pastes	4
6	Reliability testing: Thermomechanical, Mechanical shock, Electromigration, Characterization/failure analysis techniques in packaging (microscopy, surface characterization, physical properties measurements techniques)	4
7	Basics of process engineering, Statistical process control	3
8	Advanced packaging techniques: Hybrid bonding, Heterogeneous Integration, Optical interconnects, Overview of latest research papers	3
9	Specialized applications: Computing, Quantum technology, Memory, Power electronics/Automotive, Flexible electronics, MEMS & Sensors	5
10	Project: Cross section and Failure analysis of different packages	2

- Covers basics of Semiconductor Packaging with a special focus on materials and manufacturing
- Continuous improvement in the curriculum based on industry inputs
  - Process engineering, statistical process control
- Expert lectures from external industry and academia
  - Pooya Tadayon (Intel), Nachiket Raravikar (Mojo vision), Anandaroop Bhattacharya (IITKGP), Rohit Sharma (IITRPR)
- Exposure for students to industry relevant problems
  - Collaboration with Ansys, Micron, and Intel for course project



# Proposed R&D Areas - 1

## 1. Design (Electrical, Mechanical) at Assembly Level

- AI assisted modeling and design of optimized package for system level reliability and warpage management

## 2. Advanced Materials and Processes

- Low/ultra-low temperature board level assembly materials and processes
- High throughput Cu-Cu bonding at fine pitch incl. hybrid sintered bonding for large panels, glass to wafer bonding, etc.
- Board assembly and reliability of packages with complex warpage profiles (thin dies, 3D ICs, etc), large size boards
- Application specific material development (interconnects, molding/adhesives, die attach films) for warpage management at different temperatures
- Interconnect material development for quantum computing (ultra-low temperature applications)
- Sintered Cu (mixed size powder, nanoporous Cu, electric field assisted sintering)
- High reliability interconnect materials and technologies for both first level and second level interconnects
- Low temp, low pressure Cu-Cu bonding for PCB level

## 3. Advanced Prototyping

- Design and demonstrate prototypes for advanced materials and processes



# Proposed R&D Areas - 2

## 4. Metrology and Characterization

- General material property characterization incl thermal, electrical conductivity, mechanical properties
- Adhesion characterization for different interfaces in a package: die bonding/attach
- Identification of critical failures in a package
- Metrology for placement accuracy of stacked dies
- Process simulation (UF flow, flux clean, etc.)

## 5. Reliability

- Stacked dies: dynamic warpage, Rel with LTS, electromigration with LTS linking to AI assisted modeling
- DBC substrates for power electronics, its impact of TC
- Electromigration in sintered Ag, Cu, generally power electronics
- Thermal cycling (ultra low temp, ultra high temp), ageing, shock, vibration, power cycling/electromigration, combination of rel testing
- Failure mechanism understanding

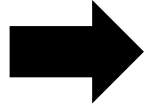
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# Process Flow for IC Assembly

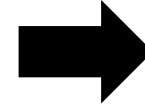
Patterning on wafer  
for bonding

Spin coater  
Mask maker  
Aligner  
Electrodeposition  
Sputtering  
Evaporator  
Plasma  
Wet bench



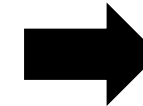
Advanced  
backgrinding and  
dicing

Tape lamination w/ UV  
cure  
Advanced back-  
grinding/ polishing tool  
Advanced dicing  
machine (Plasma,  
stealth, laser,  
ultrasonic)  
DI water system  
CMP



Assembly: Flip chip  
incl hybrid bonding,  
Wire bonding

Die pick and place  
Flip chip bonder  
Wafer bonder  
Wirebond  
Molding  
Underfill dispense  
Curing ovens with  
environment control



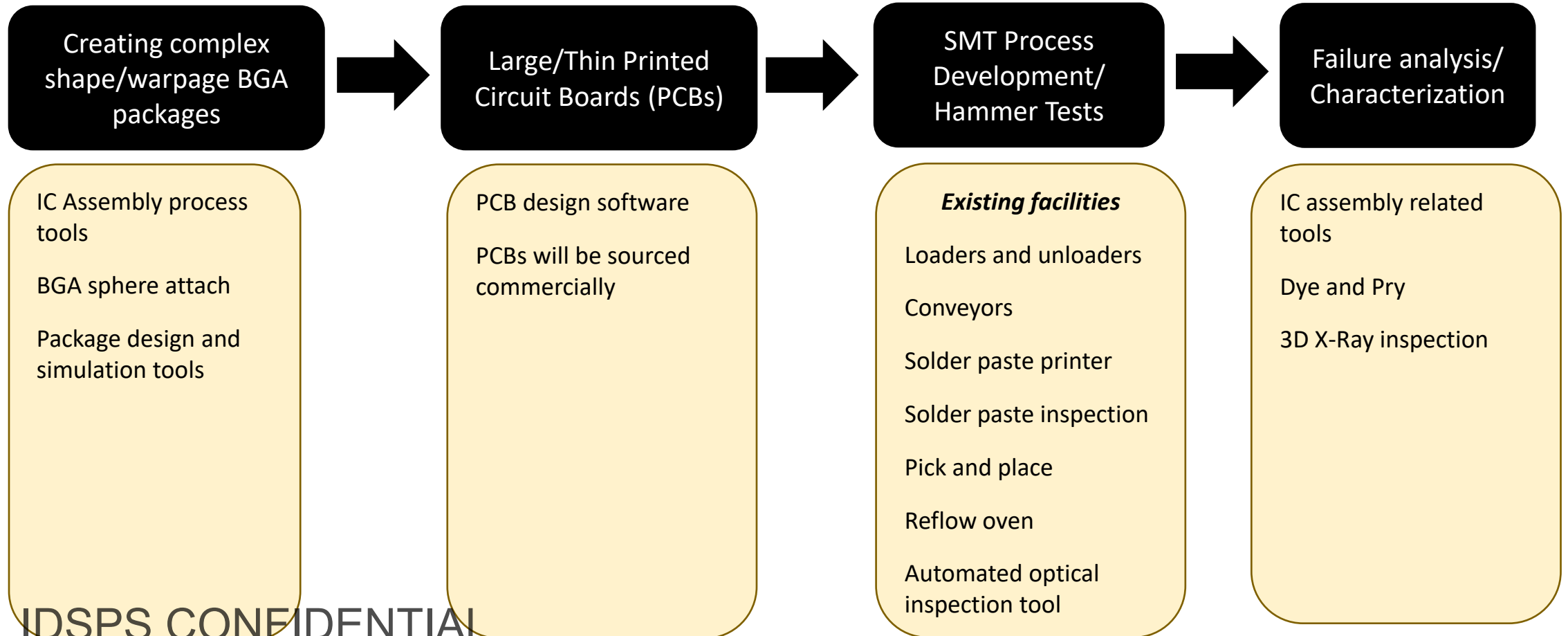
Failure analysis/  
Characterization

X-section, polishing  
Optical and confocal  
microscopes  
Shadow Moire  
CSAM  
SEM-FIB w/ EBSD & EDS  
X ray fluorescence  
TOFSIMS  
I-V Prober  
UTM, Shear tester

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# Process Flow for Board Assembly

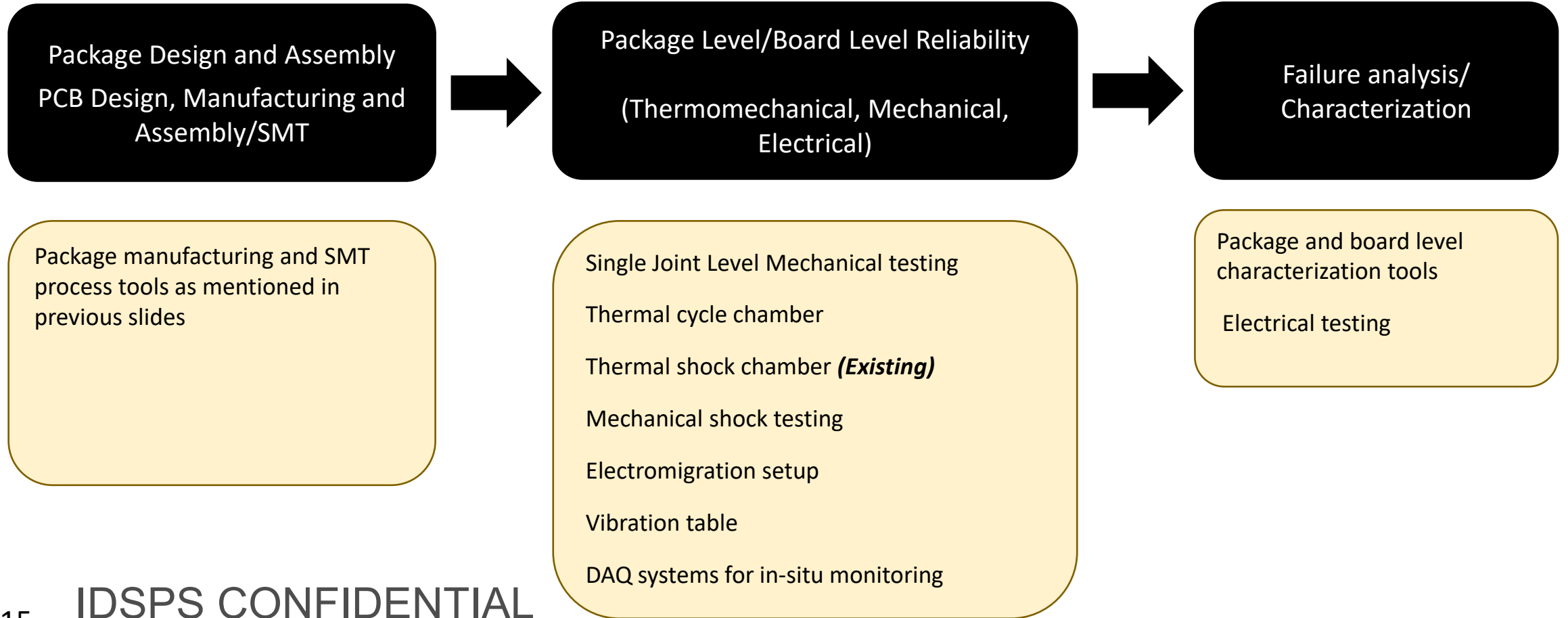


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# Process Flow for Reliability



# MacDermid Alpha Thermal Reliability Laboratory

- Initiated through the Corporate Social Responsibility (CSR) initiative of MacDermid Alpha
- Focus on skills development and research support for “Thermomechanical reliability assessment of electronic components”
- Capabilities:
  - Thermal shock testing with in-situ monitoring,
  - Aging/baking oven
  - Failure analysis facilities including PCB cross-sectioning/Diamond saw cutter, sample mounting, dual motor polishing wheel
  - Advanced Digital Microscope

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# NMTronics Center of Excellence for Electronics Manufacturing and Skills Development

- Initiated through the Corporate Social Responsibility (CSR) initiative of NMTronics India Pvt. Ltd.
- Focus on skills development, manufacturing support and research related to Electronics Manufacturing, specifically Surface Mount Technology (SMT)
- Capabilities: State-of-the-art Surface Mount Technology line including solder paste printing, solder paste inspection, pick-and-place, reflow oven, automated optical inspection
- Certificate courses at different levels including technician/operators, process engineers, and administrators/management
- Manufacturing and R&D support to industries including start-ups

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# Semiconductor Packaging Laboratory

- Planned
- Primary focus on skills development for Semiconductor Packaging
- Planned Facilities:
  - Clean room
  - Design simulation packages,
  - Wafer processing: Polishing, Dicing, Pick and place
  - IC assembly: Wirebonder, Die bonder, Molding
  - System assembly
  - Reliability and failure analysis: Thermal cycle, mechanical shock, vibration tables, cross-sectioning, optical and electron microscopes

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# List of Projects

1. Design and Demonstrate Low Temperature Fine Pitch Cu-Cu
2. Bonding on Si/Glass to Glass
3. Design and Demonstrate Low Temperature Low Pressure Nb-Nb bonding for Large Scale Qubits Integration
4. Adhesion improvement of Cu-Cu and Cu-Epoxy joints
5. Development of Low Temperature Indium-based wafer-level Bonding
6. Process Development of Sintered Cu and alloys for Die attachment application in Power Electronics
7. Systematic study of temperature-dependent properties of Sn-Bi-based low-temperature solder alloys with various alloying elements
8. Study on Optimization of High Temperature Solder Alloys Composition and Reliability Evaluation in Power Semiconductors
9. Combined Effect of Fatigue and Current on the Reliability of a SnBi based Low Temperature Solder Joints
10. Low Temperature Cu-Cu Bonding at PCB Level
11. Reliability Analysis of a Printed Circuit Board (PCB), Electronic Components and ICs

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# Design and Demonstrate Low Temperature Fine Pitch Cu-Cu Bonding on Si/Glass to Glass

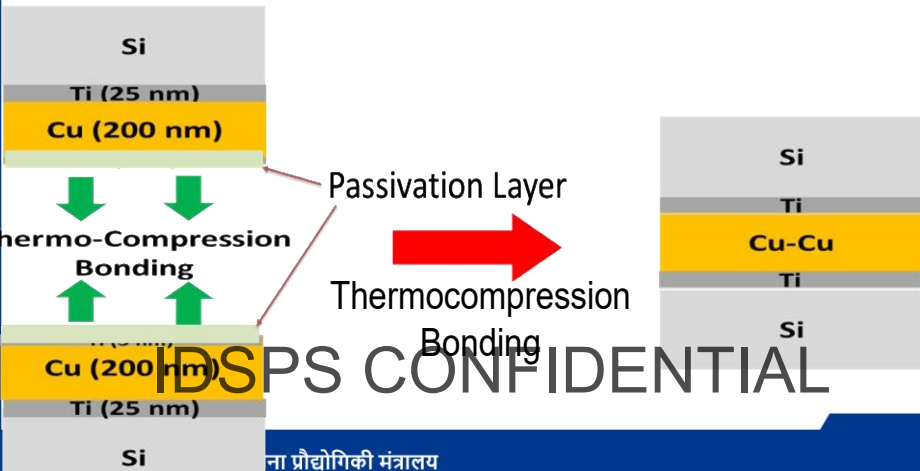
PIs: Shiv Govind Singh (IITH), Nilesh Badwe (IITK), Vanessa Smet (GaTech)

## Objective

- ❑ To develop and demonstrate ultra fine pitch VIA formation and filling in thin glass substrate.
- ❑ Surface engineering for low temperature low pressure bonding Cu-Cu Si/Glass -Glass Thermo-compression Bonding.
- ❑ Electrical, Mechanical and reliabilities studies of interconnects.

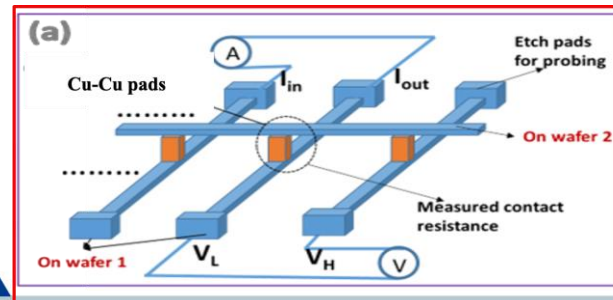
Parameters	Current state of the art (Cu-to-Cu Wafer to wafer bonding)	Proposed (Cu-Cu, Si/Glass - Glass bonding)
TGV diameter formation	15um	10-15um
Bonding temperature	<200 °C	<250 °C
Bonding pressure	<10 M Pascal	<10 M Pascal
Pitch	< 25micron	< 25micron
Specific Contact Resistance	< 10 <sup>-7</sup> ohm/cm <sup>2</sup>	< 10 <sup>-7</sup> ohm/cm <sup>2</sup>

**WP1:** Surface engineering for low temperature low pressure Cu-Cu Bonding at Si/Glass- Glass bonding

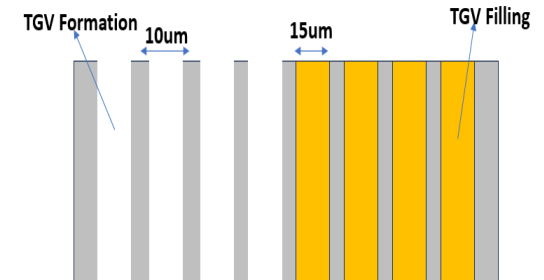


## Approach

**WP2:** Electrical, Mechanical and reliabilities studies of interconnects



**WP3:** Ultra fine pitch VIA formation and filling in thin glass substrate.



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# Design and Demonstrate Low Temperature Low Pressure Nb-Nb bonding for Large Scale Qubits Integration

PI: Shiv Govind Singh (IITH), Naresh Emani (IITH), Nilesh Badwe (IITK), Vanessa Smet (GaTech)

## Objective

- Selection of optimized superconducting interconnect materials using simulation.
- Demonstration of Low-temperature Low-pressure thermocompression bonding of selected materials.
- Electrical, Mechanical, and Reliability Studies of superconducting interconnects.

## Proposed vs. Prior Art

Parameters	Current Status	Proposed
Interconnect materials	Cu (however not suitable as Cu is not SC materials), Nb as well	Nb and still doing more simulation
Bonding temperature	Cu 150, Nb room temperature SAB treatment,	<250°C,
Bonding pressure	Cu , 9 MPascal, Nb npt reported	Sub 10 MPascal
Bond strength	Cu 113Mpascal , Not reported	>100M Pascal
Pitch	Cu, 25 um, Nb Not reported	<50 micron
Specific Contact Resistance	<10 <sup>-7</sup> ohm/cm <sup>2</sup> Cu, Nb, Not reported	< 10 <sup>-5</sup> ohm/cm <sup>2</sup> , SC below T <sub>c</sub>

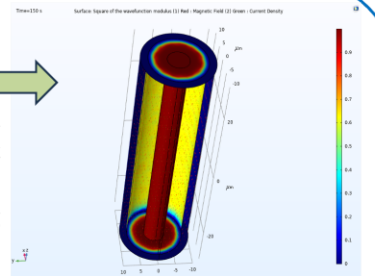
## PROPOSED APPROACH CONTINUED

### Objective -1

**Selection of optimized Superconducting Material**

**Problem:-** Interlayer dielectrics (ILDs) to isolate signals from multilayers like silicon dioxide, and silicon nitride decrease qubit lifetimes

**Solution:-** Material compatible with high-coherence qubits (Modelling and Simulation of Nb/ other superconducting material).

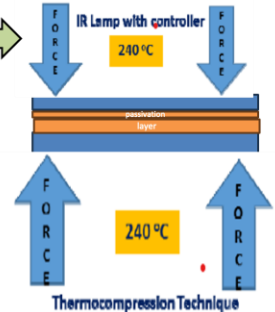


### Objective-2

**Integrate the qubit Chip and interposer**

**Problem:-** Copper is not superconducting hence metallization and electric current in these metals cause heating and exciting Quasiparticle results in qubit performance degradation

**Solution:-** Bonding of less lossy superconducting material like Nb/ other superconducting Material (Direct Bonding or using a Passivation Layer)

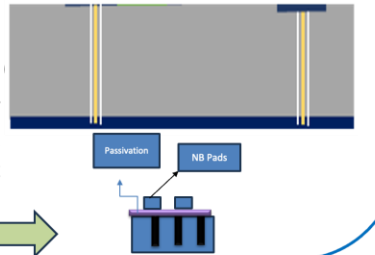


### Objective-3

**Electrical, Mechanical, and Reliability of Superconducting Bonding Interface and Array of SC Interconnect**

**Problem:-** Electrical, Mechanical, and reliability study at Cryogenic Temperature.

**Solution:-** AFM, XRD, C-SAM, SEM, EDX, and Cryogenic Test for material characterization, shear/pull test for Mechanical Characterization, I-V (normal and SC ), electromigration test, qubit coherence analysis using microwave generator.



Fujino, M., Araga, Y., Nakagawa, H., Takahashi, Y., Nanba, K., Yamaguchi, A., Miyata, A., Nishi, T. and Kikuchi, K., 2023. Interconnects. Journal of Applied Physics, 133(1).

भारत सरकार द्वारा प्रोत्साहित

Renaud, P., Dubarry, C., Bresson, N., Deschaseaux, E., Fournel, F., Morales, C., Abadie, K., Thomas, C. and Charbonnier, J., 2024, May. In 2024 IEEE 74th Electronic Components and Technology Conference (ECTC) (pp. 441-446). IEEE.



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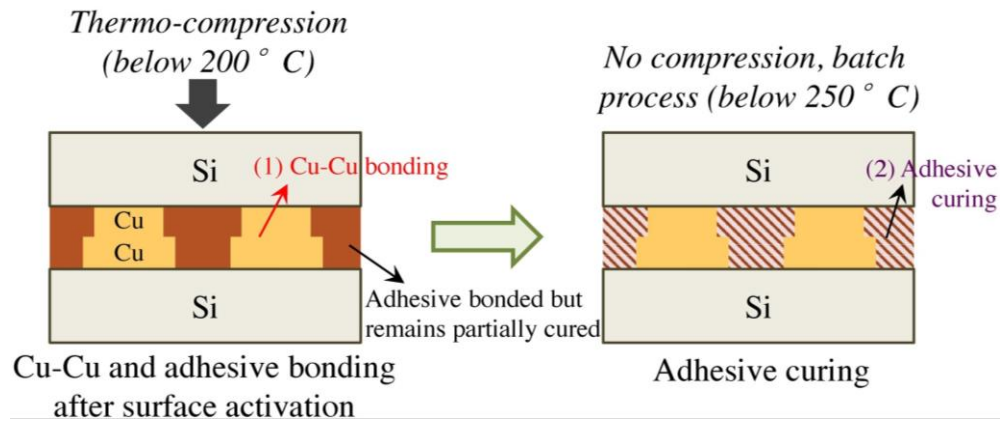
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# Adhesion improvement of Cu-Cu and Cu-Epoxy joints

PI: Poonam Sundriyal (IITKGP), Deepak Arora (IITJ), Nilesh Badwe (IITK)

**Objective:** Surface activation of Cu to improve to improve the adhesion between Cu-Cu and Cu-Epoxy joints at low temperature (room temperature to 150°C).



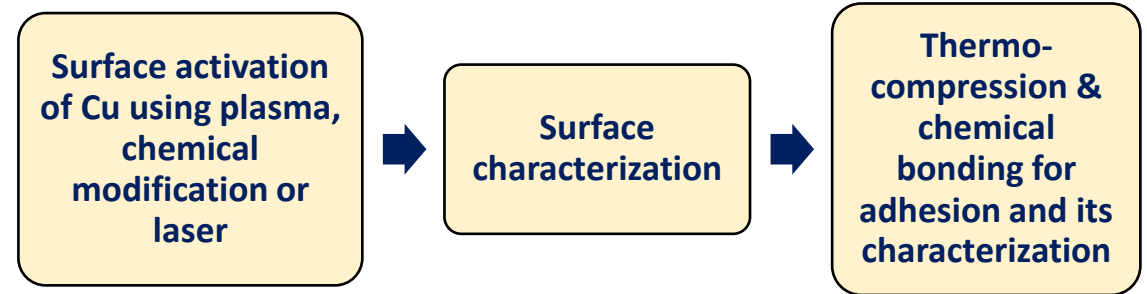
Adapted from Suga et al., 2021.

## Proposed vs. Prior Art

Parameters	Current state of the art	Proposed
Shear strength	56 MPa	>100 MPa
Temperature range	>450 °C	Room temperature to 200 °C
Wettability and Surface energy	~ 60 to 85° and low surface energy	~ 10° and high surface energy

## Approach

- ❑ The surface activation of Cu using chemical treatment, plasma, passivation, and Laser texturing.
- ❑ The surface roughness, surface energy, and functional groups of surface will be manipulated.
- ❑ The activated surfaces will form strong chemical joints at room temperature



## Outcome and Impact

- Demonstration of a suitable surface activation techniques of copper for adhesion improvement.
- Better interface adhesion will improve the quality and reliability of 3D interconnects.

Kim, S., Nam, Y. and Kim, S.E., 2016. Japanese Journal of Applied Physics, 55(6S3), p.06JC02.

Chua, S.L., Chan, J.M., Goh, S.C.K. and Tan, C.S., 2018. IEEE Transactions on Components, Packaging and Manufacturing Technology, 9(3), pp.596-605.

# Development of Low Temperature Indium-based wafer-level Bonding

PI: Pradeep Dixit (IIT Bombay)

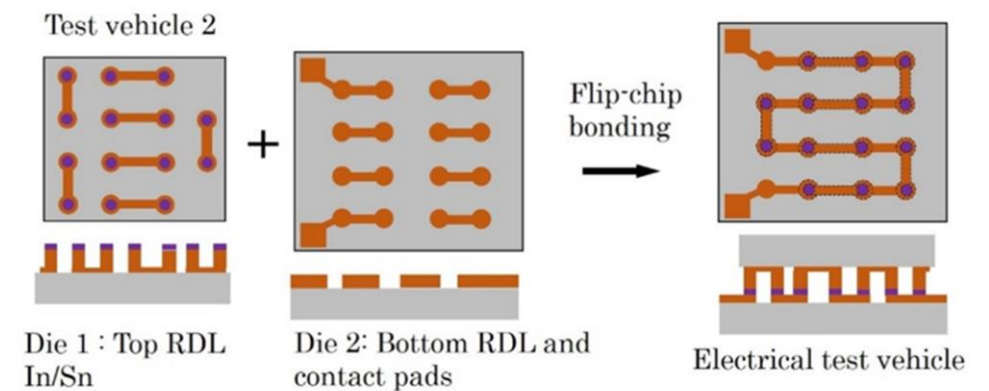
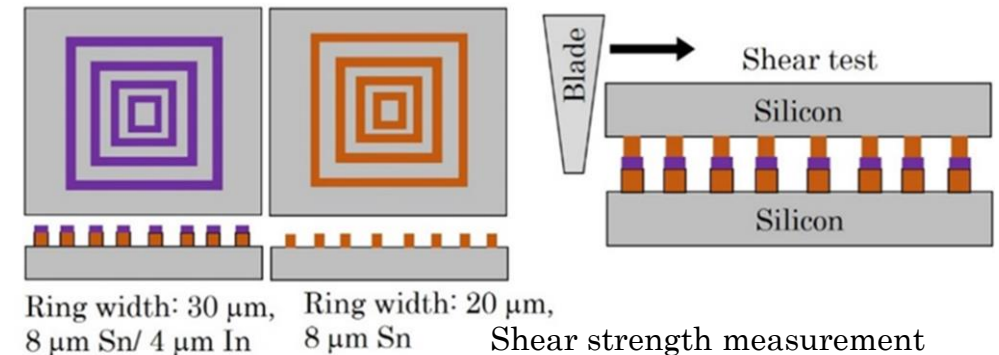
Objective: To develop and demonstrate low-temperature (<200°C) Indium-based bonding for wafer-level packaging

Prior art Vs proposed R&D:

	Current state	Proposed
Material	Sn-based solder alloys	In-based alloys
Pitch	< 50 $\mu\text{m}$	< 50 $\mu\text{m}$
Bonding temperature	>250 $^{\circ}\text{C}$	<200 $^{\circ}\text{C}$
Uniformity	$\pm 5\%$	$\pm 5\%$

Technical Challenges:

- Demonstrate wafer-scale indium electroplating with  $\pm 5\%$  uniformity
- Solder based flip chip bonding for fine pitch and low temperature bonding
- Wet chemical etching of seed layer without affecting indium bumps
- Reliability of low temp bonded-assembly



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# Process Development of Sintered Cu and alloys for Die attachment application in Power Electronics

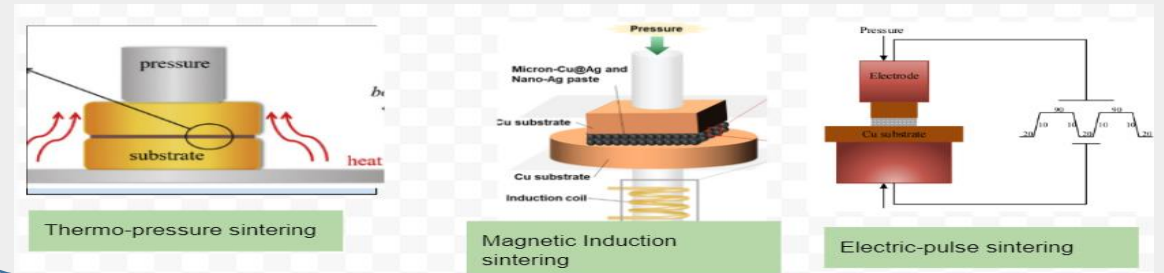
Pradipta Ghosh (IITGN), Komal Kumar (IITGN), Nilesh Badwe (IITK)

**Objective:** Discover new alloys and develop processes for defect free die attachment for high temperature (>300°C) Power electronics.

- Identify proper material and sintering environment for low sintering temperature (150°C-250°C)
- Explore different heating methods for sintering and quantify their effect on kinetics of sintering
- Quantify the thermo-mechanical reliability and electromigration in sintered material

**Proposed Method:** Thermo pressure based sintering of Cu powders, Cu@Ag powder with reducing agents using:

- (1) Thermo-pressure sintering
- (2) Electric pulse sintering
- (3) Magnetic induction sintering



## Industry need:

Material and Process	Advantages	Disadvantages
High Temperature Solders (Au-In, Ag-Au-Ge, Ag-Cu eutectics)	High $T_{Operation}$	High $T_{bonding}$ , Cost
TLP Bonding (Ag/In, Au-In)	Low $T_{Bonding}$ and high $T_{Operation}$	Long Bonding time, Void formation, Brittle IMC
Ag/Cu powder sintering	Low $T_{Bonding}$ and high $T_{Operation}$	Ag (Costly, electromigration); Cu (oxidation)

## Comparison of Proposed and Prior art:

Parameters	Current state of the art	Proposed
Conventional Sintering $T$ (°C)/ time (min)/ $P$ (MPa)	300-500/ 5-15/ ~10-40	< 250/ ~1-5/<5
Electric pulse assisted sintering CD ( $A \cdot mm^{-2}$ )	200 for copper powders	Thermal + current Cu-NP size, chemistry
Induction heating	Ag powders Ag coated Cu powders	Cu-NP, Cu@Ag size, chemistry

# Systematic study of temperature-dependent properties of Sn-Bi-based low-temperature solder alloys with various alloying elements

Nilesh Badwe (IITK), Pradipta Ghosh (IITGN), Shiv Govind Singh (IITH)

## Objective

To create a knowledge base of the impact of different alloying elements and their concentrations on the physical and mechanical properties of SnBi based low temperature solders (LTS) over a temperature range relevant to electronics

## Approach

- **Synthesis** of the Sn-Bi-based LTS Solder doped with Ag, Cu, Sb, In, Co, and Ni with concentrations 0-1 wt.% respectively
- **Microstructural Characterization:** IMC thickness/composition on CuOSP and ENIG substrate coupon pre and post ageing
- **Physical properties:** Resistivity, Temperature coefficient of resistance, Melting and solidification behaviour
- **Thermomechanical Properties:** Tensile testing and low cycle fatigue testing at (-40°C, -20°C, 0°C, 25°C, 85°C, 100°C)

## Proposed vs Prior Art

Parameters	Composition	Current state of Art	Proposed
Temperature-dependent tensile properties	Eutectic Sn-58Bi	Limited	Yes
	Other alloying elements	No	Yes
Temperature-dependent fatigue performance	Eutectic Sn-58Bi	No	Yes
	Other alloying elements	No	Yes
Temperature dependant resistivity	Eutectic Sn-58Bi	Limited	Yes
	Other alloying elements	No	Yes

Kamaruzzaman, L.S. and Goh, Y., 2022. *Soldering & Surface Mount Technology*, 34(5), pp.300-318.  
Mokhtari, O. and Nishikawa, H., 2016. *Materials Science and Engineering: A*, 651, pp.831-839.



# Study on Optimization of High Temperature Solder Alloys Composition and Reliability Evaluation in Power Semiconductors

Ajay Kumar (IITT), Nilesh Badwe (IITK)

- **Objective:** To optimize the composition of high-temperature solder alloys and study their long-term reliability

## Approach:

- **Synthesis:** Select appropriate solder alloy compositions and design based on the impact of extreme conditions on the reliability and durability of solder joints
- **Characterization and Testing:**
- Microstructure evolution, Interfacial reactions, characteristics of IMCs
- Mechanical shear performance, creep resistance and failure analysis
- Corrosion resistance
- The creep strength at the reliability design stage of the packaging (300°C-400°C)
- Reliability mapping

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## Proposed Vs Prior Art:

Parameters	Composition	Current State of Art	Proposed
Long-term reliability at high-temperature	Au-Sn, Au-Ge, Zn-Al, Zn-Sn, Sn-Sb, Bi-Ag	No	Yes
Creep Resistance	Au-Sn	No	Yes
Interfacial reactions, characteristics of IMCs	Au-Ge, Au-In, Ag-Cu	No	Yes
Grain size control, corrosion resistance	Zn-Al, Zn-Sn	No	Yes
Interfacial reaction and solder joint strength	Sn-Sb, Au-Ag-Ge, Bi-Ag	No	Yes

Reliability and Durability

Extended Operational Lifespan

Manufacturability and Cost Savings

Reduced Downtime

1. Morshed, M, Y Wang, L R. Billa, T Grant, M Mat, and D Payne" In *PCIM Europe 2023; International Exhibition and Conference for Power Electronics, Intelligent Motion, Renewable Energy and Energy Management*, pp. 1-5. VDE, 2023.

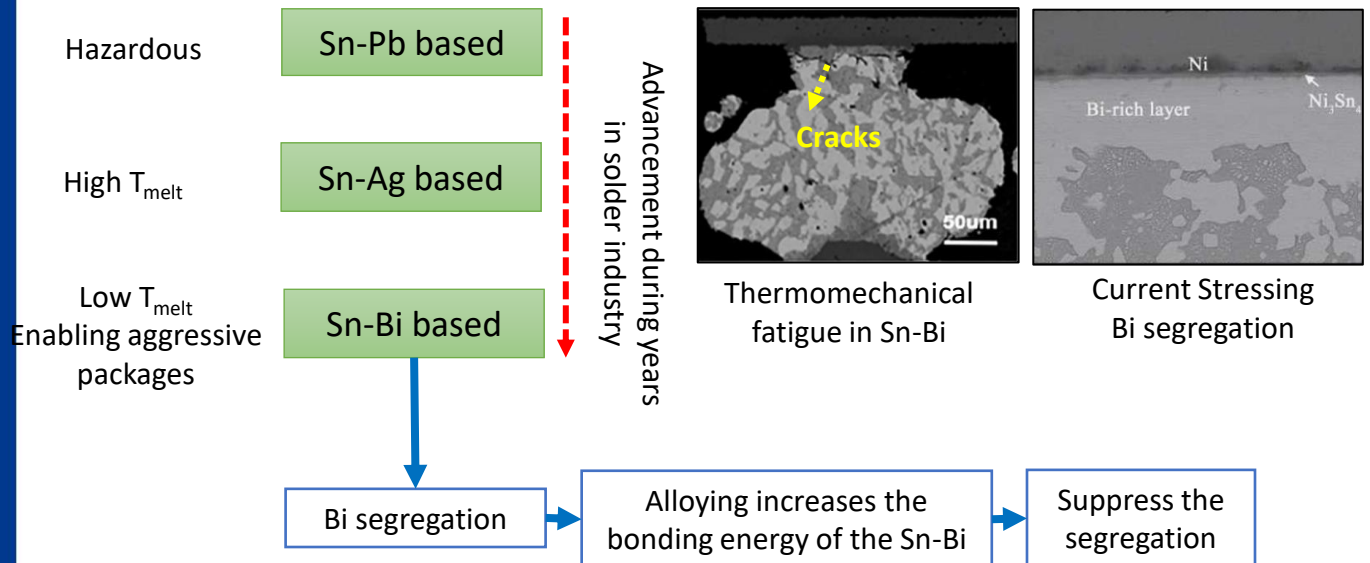
2. Zeng, G, S McDonald, and K Nogita." *Microelectronics Reliability* 52, no. 7 (2012): 1306-1322.



# Combined Effect of Fatigue and Current on the Reliability of a SnBi based Low Temperature Solder Joints

Nilesh Badwe (IITK), Ajay Kumar (IITT) and Pradipta Ghosh (IITGN)

**Objective -** To study the combined effect of fatigue and current on the life of Sn-Bi based solder alloy joint with a focus on performance improvement through alloying elements Sb, In, and Ag

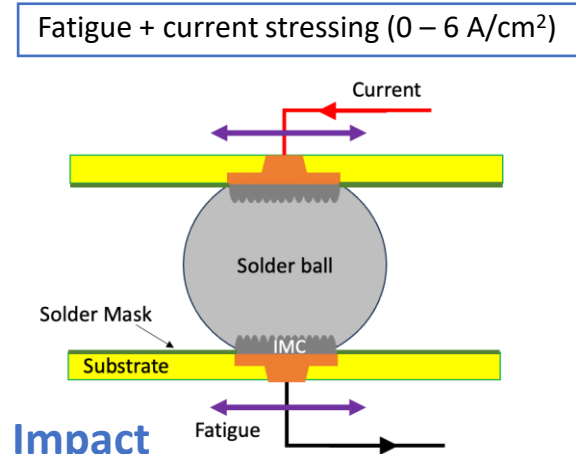


## Proposed vs. Prior Art

Parameters	Current State	Proposed
Combined effect of fatigue and current	Package level	Controlled joint level
Effect of alloying elements on fatigue and current stressing	No	Yes
Solder joint level study to include IMC impact	No	Yes

## Approach

- Alloying of 0-1% of Sb, In & Ag homogenization through multiple melting cycle
- Solder joint formation through preforms



## Outcome and Impact

- Study the effect of failure mechanism and effect of alloying
- Design, synthesis, and characterization
- Model development to separate the effect of current and fatigue on an individual solder joint life

Surendar, A., Kishore, K.H., Kavitha, M., Ibatova, A.Z. and Samavatian, V., 2018.. *IEEE Transactions on Device and Materials Reliability*, 18(4), pp.606-612  
 Long, X., Liu, Y., Jia, F., Wu, Y., Fu, Y. and Zhou, C., 2019. *Journal of Materials Science: Materials in Electronics*, 30, pp.7654-7664..

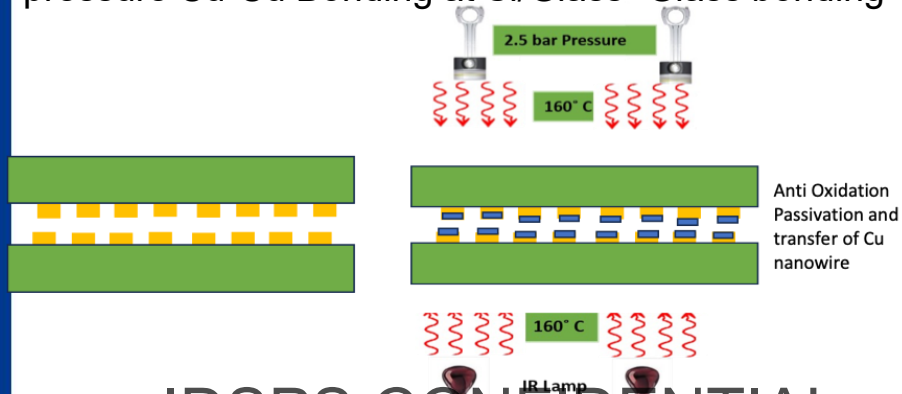
# Low Temperature Cu-Cu Bonding at PCB Level

PIs: Shiv Govind Singh (IITH), Nilesh Badwe (IITK), Vanessa Smet (GaTech)

## Objective

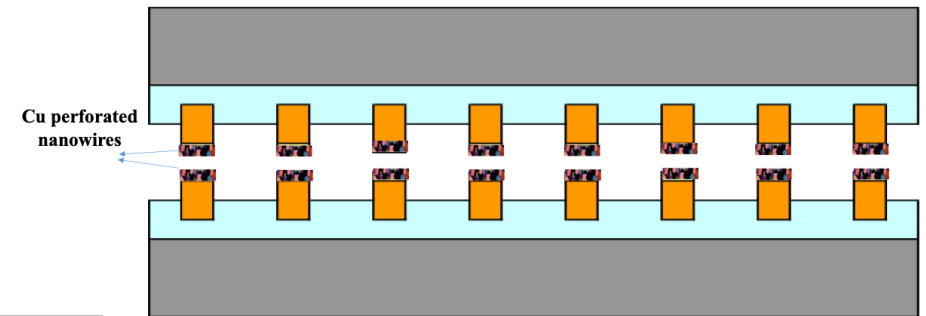
- Design and fabricate Cu pad at PCB akin to normal PCB used for assembly.
- Surface engineering for demonstration of low temperature low pressure bonding.
- Electrical, Mechanical and reliabilities studies of interconnects.

**WP1:** Surface engineering for low temperature low pressure Cu-Cu Bonding at Si/Glass- Glass bonding



## Approach

**WP2:** Warpage utilize perforated Cu nanowires on top of Cu pad/trace to address the variation on top of surface passivation



Parameters	Current state of the art (Solder bonding/ paste)	Proposed (solderless bonding)
Cu-Cu bonding PCB level	Solder use, ~160°	< 200°C
Bond strength	8 - 18 MPa	> 50 MPa
Bonding Pressure	0 - 1.8 MPa	< 2 MPa
Pitch	100 μm	< 50 μm
Cu Trace	~ 50 μm/Blanket	25 μm

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Cao, Z., Lehmann, J., Heusdens, B., Durmaz, E.C., Krüger, P., Wietstruck, M., Herfurth, N., Adesunkanmi, A.A., Carta, C. and Kaynak, M., 2024 IEEE Transactions on Components, Packaging and Manufacturing Technology.

Jangam, S., Bajwa, A.A., Mogera, U., Ambhore, P., Colosimo, T., Chylak, B. and Iyer, S., 2019t. In 2019 IEEE 69th electronic components and technology conference (ECTC) (pp. 620-627). IEEE.

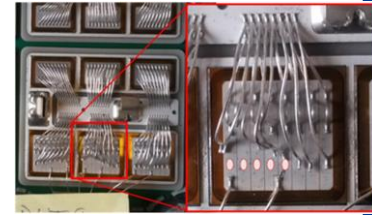


# Reliability Analysis of a Printed Circuit Board (PCB), Electronic Components and ICs

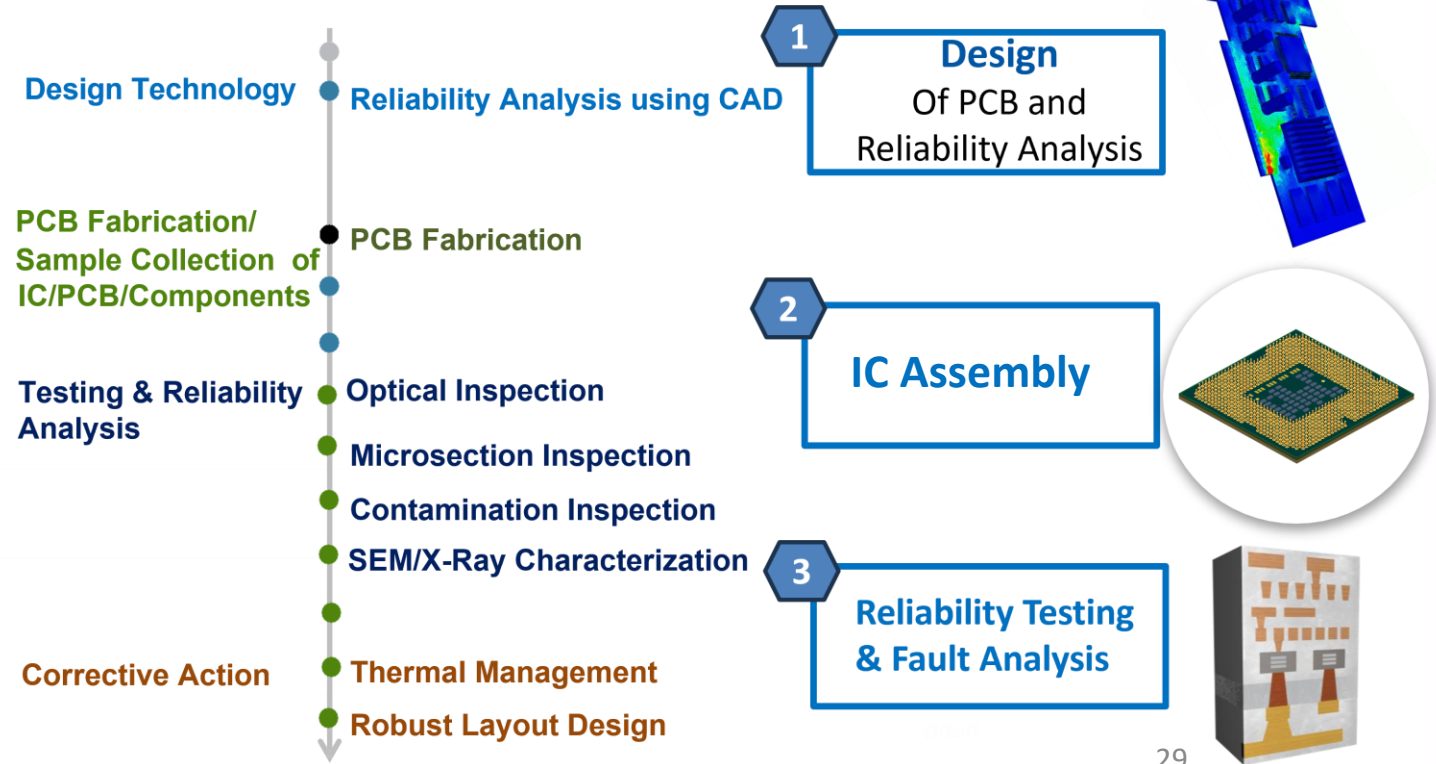
Team: Dr. Soumyaranjan Routray (SRM), Prof. Shanthi Prince (SRM), Prof. P. Eswaran (SRM)

## Objectives:

- Reliability Analysis of Electronic Components and PCB using CAD Tool/DFT Analysis
- Understanding the failure modes and failure mechanisms of PCB/Component failure
- Corrective Action to improve reliability



## Approach:



	Current state*	Proposed
<b>Reliability Issue</b>	conductive anodic filament (CAF)	CAF Resistant
<b>Microcrack</b>	De-penalization	modified de-penalization method
<b>Electromagnetic Induced Failure</b>	Crack or Pit shape defects	Radiation resistant design for components
<b>Thermal Stress/Surface degradation</b>	Breakdown of components and Traps	Finding root cause of failure

Hill, P. Chanawala, R. Singh, S. A. Sheikholeslam and A. Ivanov, "CMOS Reliability From Past to Future: A Survey of Requirements, Trends, and Prediction Methods," in *IEEE Transactions on Device and Materials Reliability*, vol. 22, no. 1, pp. 1-10, March 2022

## Global Collaboration:

Prof. Cher Ming Tan, Director, Centre for Reliability Sciences and Technologies (CreST), Chang Gung University, Taiwan

# 5 Year Plan/Timeline

Milestones	Year 1	Year 2	Year 3	Year 4	Year 5
Submit Proposal	█				
Identify industry partners	█				
Set up industry consortium	█	█			
Set up infrastructure		█	█		
Develop Research Programs		█	█	█	█
Develop Educational Programs		█	█	█	█
Demonstrate Technologies			█	█	█
Integrate Technologies into Industry Prototype 1			█	█	█
Integrate Technologies into Industry Prototype 2				█	█
Integrate Technologies into Industry Prototype 3					█

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# Industry Needs (Intel)

- SoC (Silicon area) for computing/AI is growing at an unprecedented rate → 2.5D, 3D & 3.5D
- Package area grows because of SoC (2.5x-4x) as well as I/O count and higher power (TDP) requirements
- >10K mm substrate area with 1000s of I/Os
- Higher I/O speed → GND pins → overall pin count and substrate size
- Assembly of large BGA → LTS → current carrying capability improvement

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